IN THE CLAIMS

1. (Currently amended) A method of exposure error adjustment in photolithography for multiple products, comprising the steps of:

determining if the product to be processed is a secondary product;

choosing a photo feedback system (PFBS) start value;

providing a standard point;

providing an offset difference;

evaluating ~~providing~~ a compensation difference; and

calculating a photo feedback system (PFBS) parameter to evaluate an adjustment value of each operation for automatic adjustment.

2. (Currently amended) The method of claim 1, wherein the step of choosing the photo feedback system (PFBS) start value is a decision ~~of~~ regarding the photo feedback system (PFBS) start value suited to ~~a host~~ the product to be processed ~~or a miscellaneous product~~.

3. (Original) The method of claim 2, wherein the standard point for the host product is the photo feedback system (PFBS) parameter of the host product last processed.

4. (Original) The method of claim 2, wherein the compensation difference for the host product is an actual exposure error of the host product last processed.

5. (Currently amended) The method of claim 2, wherein the standard point for the ~~miscellaneous~~ secondary product is the photo feedback system (PFBS) parameter of the host product in a ~~nearest~~ most recent operation.

6. (Currently amended) The method of claim 2, wherein the compensation difference for the ~~miscellaneous~~ secondary product comprises ~~a~~ an offset difference between the host product and the ~~miscellaneous~~ secondary product and the actual error of the ~~miscellaneous~~ secondary product last processed.

7. (Currently amended) The method of claim 6, wherein the offset difference between the host product and the ~~miscellaneous~~secondary product is a value difference in

the photo feedback system (PFBS) parameter between the ~~miscellaneous~~ secondary product last processed and the host product in the ~~nearest~~ most recent operation.

8. (Currently amended) A method of exposure deviation error adjustment for multiple products, comprising the steps of:

determining if the product to be processed is a secondary product;

choosing a photo feedback system (PFBS) start value suited to the ~~a host~~ product ~~or a miscellaneous product~~ to be processed;

providing a photo feed-back system (PFBS) parameter evaluated from the host product in a ~~nearest~~ most recent operation as a standard point;

providing an offset difference;

evaluating ~~providing~~ a compensation difference; and

calculating the photo feedback system (PFBS) parameter to evaluate an adjustment deviation of each exposure operation for automatic adjustment.

9. (Original) The method of claim 8, wherein the photo feedback system (PFBS) parameter is the adjustment deviation.

10. (Original) The method of claim 8, wherein the compensation difference for the host product is an actual deviation error of the host product last processed.

11. (Currently amended) The method of claim 8, wherein the compensation difference for the ~~miscellaneous~~ secondary product comprises ~~a~~ an offset difference between the host product and the ~~miscellaneous~~ secondary product and the actual deviation error of the ~~miscellaneous~~ secondary product last processed.

12. (Currently amended) The method of claim 11, wherein the offset difference between the host product and the ~~miscellaneous~~ secondary product is a value difference in the photo feedback system (PFBS) parameter between the ~~miscellaneous~~ secondary product last processed and the host product in the ~~nearest~~ most recent operation.

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13. (Currently amended) A method of exposure critical dimension (CD) loss adjustment for multi-product, comprising the steps of:

determining if the product to be processed is a secondary product;

choosing a photo feedback system (PFBS) start value suited to ~~a host~~ the product ~~or a miscellaneous product~~ to be processed;

providing a photo feed-back system (PFBS) parameter evaluated from the host product in a nearest operation as a standard point;

providing an offset difference;

~~providing~~ evaluating a compensation difference; and

calculating the photo feedback system (PFBS) parameter to evaluate an adjustment critical dimension (CD) of each exposure operation for automatic adjustment.

14. (Original) The method of claim 13, wherein the photo feedback system (PFBS) parameter is the adjustment critical dimension (CD).

15. (Original) The method of claim 13, wherein the compensation difference for the host product is an actual critical dimension (CD) loss of the host product last processed.

16. (Currently amended) The method of claim 13, wherein the compensation difference for the ~~miscellaneous~~ secondary product comprises ~~a~~ an offset difference between the host product and the ~~miscellaneous~~ secondary product and the actual critical dimension (CD) loss of the ~~miscellaneous~~ secondary product last processed.

17. (Currently amended) The method of claim 16, wherein the offset difference between the host product and the ~~miscellaneous~~ secondary product is a value difference in the photo feedback system (PFBS) parameter between the ~~miscellaneous~~ secondary product last processed and the host product in the ~~nearest~~ most recent operation.

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